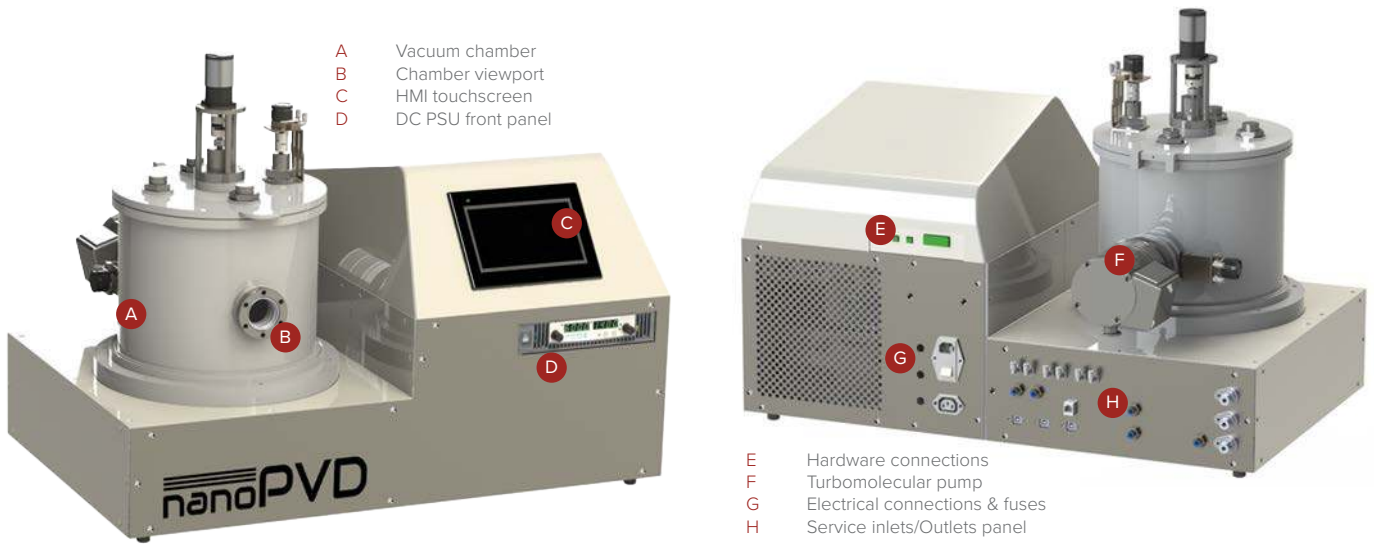


nanoPVD-S10A-WA by Moorfield.

Research-grade magnetron sputtering.
Wide area configuration.



MOORFIELD
— NANOTECHNOLOGY —

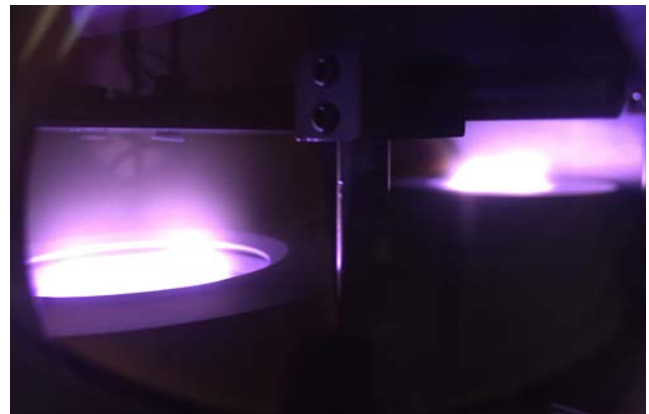


Benchtop, turnkey system for high performance RF and DC magnetron sputtering onto substrates up to 8” diameter. Compact as an electron microscopy coater, but with research-grade results.

Recently introduced, nanoPVD model S10A is a magnetron sputtering system designed for repeatable coating of metals or inorganics (e.g., oxides or nitrides). Compact and suitable for benchtop location, nanoPVD systems are derived from proven R&D thin-film system technology and have been developed through extensive collaboration with leading academic groups. The tools are optimised for ease of use, represent outstanding value for money and are ideal where available space and budgets are key considerations—without compromising on performance.

While the standard model S10A is suitable for substrates up to 4” diameter, the wide-area (WA) configuration extends this to substrate diameters up to 8”.

- Application-specific configuration for the nanoPVD-S10A
- Uniform coating for substrates up to 8” diameter
- Benchtop configuration
- Up to 2 × 2” magnetron sputtering sources
- Up to 3 MFC-controlled process gases
- DC and/or RF power options
- Fully automatic operation via touchscreen HMI
- Turbomolecular pumping system
- Base pressures 5×10^{-7} mbar
- Define/save multiple process recipes
- Automatic pressure control option
- Equipped for easy servicing
- Comprehensive safety features
- Cleanroom compatible
- Proven performance



Wide area configuration for the nanoPVD S10A

Visit moorfield.co.uk or call +44(0) 1565 722609